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GNE518US ARI.027

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In repatent application of:

Allowed: February 10, 2006

Noboru MORITA et al.

Serial No.: 10/766,921

Group Art Unit: 2818

Filing Date: January 30, 2004

Examiner: David Nhu

For:

METHOD OF FABRICATING SEMICONDUCTOR DEVICE USING

PLASMA-ENHANCED CVD

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

REQUEST FOR CONSIDERATION OF FORMAL DRAWINGS

Sir:

Applicant respectfully requests that the formal drawings submitted and filed on January 30, 2004 be officially considered of record.

A Notice of Allowability was issued on February 10, 2006. However, the Notice of Allowability did not indicate whether or not the formal drawings had been accepted.

Therefore, Applicant respectfully requests that the Examiner officially acknowledge the formal drawings submitted on January 30, 2004. For the Examiner's convenience submitted herewith is another copy of the Formal Drawings.

Respectfully submitted,

Sean M. McGinn, Esq.

Registration No.: 34,386

Date:

MCGINN INTELLECTUAL PROPERTY

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